

Resource Summary Report

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Oxford: PlasmaPro 100 Cobra Plasma Technology

RRID:SCR_020371

Type: Tool

Proper Citation

Oxford: PlasmaPro 100 Cobra Plasma Technology (RRID:SCR_020371)

Resource Information

URL: <https://plasma.oxinst.com/products/icp-etching/plasmapro-100-icp>

Proper Citation: Oxford: PlasmaPro 100 Cobra Plasma Technology (RRID:SCR_020371)

Description: PlasmaPro 100 Cobra ICP utilises high density plasma to achieve etching and deposition rates. Process modules offer uniformity, high throughput, high precision and low damage processes for wafer sizes up to 200mm.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: PlasmaPro 100 Cobra Plasma Technology

Resource ID: SCR_020371

Alternate IDs: Model_Number_100_Cobra

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260801T190656+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 100 Cobra Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 100 Cobra Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.